

- [08] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
Evaluation of the MRR control performance of PCVM with the application of the PWM control
○Y. Takeda, Y. Hata, J. Ito, K. Endo, K. Yamamura

- [07] 2014/02/06@Osaka in Japan
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Optimization of water content in process gas for high MRR of single crystal diamond in plasma assisted polishing
○T. Tabata, K. Monna, Y. Yamamoto, S. Makiyama, H. Deng, K. Endo, K. Yamamura

- [06] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
Development of two-stage figuring process applying numerically controlled electrochemical machining for fabricating neutron focusing mirror substrate
○N. Mitsushima, M. Ouchi, K. Endo, K. Yamamura

- [05] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
Effects of water concentration and gas species on OH radical emission intensity in plasma assisted polishing
○K. Monna, H. Deng, T. Tabata, K. Endo, K. Yamamura

- [04] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
XTEM observation of the anodic oxide layer/SiC interface morphology during anodic oxidation assisted polishing
○K. Hosoya, Y. Imanishi, K. Endo, K. Yamamura

- [03] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
Nanoindentation studies on the mechanical properties of silicon face and carbon face of 4H-SiC
○H. Deng, K. Endo, K. Yamamura

- [02] 2014/02/06@Osaka in Japan
International Workshop on Atomically Controlled Fabrication Technology
Profile measurement of aspheric mirror using High-Speed Nanoprofiler
○K. Okuda, K. Usuki, T. Kitayama, T. Kojima, K. Okita, R. Tokura, M. Nakano, R. Kudo, K. Yamamura, K. Endo

● [01] 2014/02/05@Osaka in Japan

International Workshop on Atomically Controlled Fabrication Technology

Development of precisely controlled metalodielectric plasmonic nanoshell arrays with nanogap for sensitive detection of molecular adsorption based on NIR responsive LSPR

○S. Uchida, N. Zettsu, K. Yamamura, K. Endo